

## PALM INTRANET

Day : Monday  
Date: 3/8/2004  
Time: 14:53:01

## Inventor Information for 10/627894

Inventor Name	City	State/Country
WALDFRIED, CARLO	FALLS CHURCH	VIRGINIA
HAN, QINGYUAN	COLUMBIA	MARYLAND
ESCORCIA, ORLANDO	FALLS CHURCH	VIRGINIA
ALBANO, RALPH	COLUMBIA	MARYLAND
BERRY, IVAN L	ELLICOTT CITY	MARYLAND
SHIOTA, ATSUSHI	USHIKU	JAPAN

Appln Info

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## PALM INTRANET

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## Inventor Name Search Result

Your Search was:

Last Name = SHIOTA  
First Name = ATSUSHI

Application#	Patent#	Status	Date Filed	Title	Inventor Name 21
10726666	Not Issued	020	12/04/2003 <i>all</i>	INSULATION FILM <i>Product &amp; Comp</i> <i>no pre pub</i>	SHIOTA, ATSUSHI <i>IFW</i>
10627894	Not Issued	030	07/24/2003	FLUORINE-FREE PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	SHIOTA, ATSUSHI
10346560	Not Issued	030	01/17/2003	FLUORINE-FREE PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	SHIOTA, ATSUSHI
10307384	Not Issued	168 <i>add</i>	12/02/2002	PROCESS FOR PRODUCING SILICA-BASED FILM, SILICA-BASED FILM, INSULATING FILM, AND SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI
10270066	Not Issued	168 <i>add</i>	10/15/2002	PROCESS FOR PRODUCING SILICA-BASED FILM, SILICA-BASED FILM, INSULATING FILM, AND SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI
10255941 <i>2003007746</i>	Not Issued	071 <i>add</i>	09/27/2002	STACKED FILM, INSULATING FILM AND SUBSTRATE FOR SEMICONDUCTOR	SHIOTA, ATSUSHI <i>IFW</i>
10252607 <i>2003005798</i>	Not Issued	041 <i>1712</i>	09/24/2002 <i>428/477</i>	METHOD OF FILM FORMATION, INSULATING FILM, AND SUBSTRATE FOR SEMICONDUCTOR	SHIOTA, ATSUSHI <i>IFW</i>
10252606 <i>1/2 prod; 1/2 prepub</i>	Not Issued	090 <i>1712</i>	09/24/2002 <i>428/477</i>	STACKED FILM, METHOD FOR THE FORMATION OF STACKED FILM, INSULATING FILM, AND SUBSTRATE FOR SEMICONDUCTOR	SHIOTA, ATSUSHI <i>IFW</i>
10165324	Not Issued	071 <i>1712</i>	06/10/2002	METHOD FOR THE FORMATION OF SILICA FILM, SILICA FILM, INSULATING FILM, AND SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI <i>IFW</i>
10103996 <i>Composition of Dup. Comp</i>	Not Issued	041 <i>1712</i>	03/25/2002 <i>428/477</i>	COMPOSITION FOR FILM FORMATION, METHOD OF FILM FORMATION, AND SILICA-BASED FILM	SHIOTA, ATSUSHI <i>IFW</i>
10094647	Not Issued	041	03/12/2002	METHOD OF FORMING DUAL DAMASCENE STRUCTURE	SHIOTA, ATSUSHI <i>IFW</i>
10014593	6558747	150	12/14/2001	METHOD OF FORMING INSULATING FILM AND PROCESS FOR PRODUCING SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI
09778822	6406794	150	02/08/2001	FILM-FORMING COMPOSITION	SHIOTA, ATSUSHI
09770289	Not Issued	041 <i>1712</i>	01/29/2001	PROCESS FOR PRODUCING SILICA-BASED FILM, SILICA-BASED FILM, INSULATING FILM, AND SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI <i>IFW</i>
09670547	6410151	150	09/27/2000	COMPOSITION FOR FILM FORMATION, METHOD OF FILM FORMATION, AND INSULATING FILM	SHIOTA, ATSUSHI
09669859	6410150	150	09/27/2000	COMPOSITION FOR FILM FORMATION, METHOD OF FILM FORMATION, AND INSULATING FILM	SHIOTA, ATSUSHI
09163008	6190833	150	09/30/1998	RADIATION-SENSITIVE RESIN COMPOSITION	SHIOTA, ATSUSHI

09126953	Not Issued	161	07/31/1998	LAMINATED MATERIAL FOR MULTI- LAYERED PRINTED CIRCUIT BOARDS AND MULTI-LAYERED PRINTED CIRCUIT BOARD USING THE SAME	SHIOTA , ATSUSHI
08713875	5773178	150	09/13/1996	PROCESS FOR PRODUCING A PATTERNED ANISOTROPIC POLYMERIC FILM	SHIOTA , ATSUSHI
08510867	5811504	150	08/03/1995	LIQUID CRYSTALLINE EPOXY MONOMER AND LIQUID CRYSTALLINE EPOXY RESIN CONTAINING MESOGEN TWINS	SHIOTA , ATSUSHI
08023471	Not Issued	166	02/25/1993	RESIN COMPOUND	SHIOTA , ATSUSHI

Inventor Search Completed: No Records to Display.

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Search Another: Inventor	shiota	atsushi	Search

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*from overlapping case*

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**Inventor Name Search Result**

Your Search was:

Last Name = ALBANO

First Name = RALPH

Application#	Patent#	Status	Date Filed	Title	Inventor Name 5
<i>W/ HQ</i> 10627894	Not Issued	030	07/24/2003	FLUORINE-FREE PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	ALBANO, RALPH
<i>N/ HQ</i> 10346560	Not Issued	030	01/17/2003	FLUORINE-FREE PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	ALBANO, RALPH
<i>removed this case</i> 09952649	Not Issued	061	09/14/2001	PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	ALBANO, RALPH
<i>N/ HQ these are previously removed</i> 09952398	Not Issued	071	09/14/2001	ULTRAVIOLET CURING PROCESS FOR POROUS LOW-K MATERIALS	ALBANO, RALPH
<i>N/ HQ millions removed</i> 09906276	Not Issued	071	07/16/2001	PLASMA CURING OF MSQ-BASED POROUS LOW-K FILM MATERIALS	ALBANO, RALPH

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